ABSTRACT

Provided is a substrate processing apparatus including a cooling controller which acquires information about the temperature of a heater and/or the temperature of a process chamber, the opening state of a cooling valve, and an exhaust fan, and regulates the opening state of the cooling valve to minimize an error between a predicted temperature column calculated in accordance with a prediction model and a target temperature column calculated according to the rate of change from a current target temperature to a final target temperature.

FIG. 2